

Docket No. 50184

IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

APPLICANT: Mori et al.

SERIAL NO.: 08/726,613

FILED: October 7, 1996

FOR: DYED PHOTORESISTS AND METHODS AND ARTICLES OF  
MANUFACTURE COMPRISING SAME



GROUP: 1752

EXAMINER: J. Chu

RECEIVED  
JUL 19 1999  
1700 MAIL ROOM

THE HONORABLE COMMISSIONER OF PATENTS AND TRADEMARKS  
WASHINGTON, DC 20231

SIR:

**AMENDMENT AFTER FINAL REJECTION**

Applicants are in receipt of the Final Office Action dated July 7, 1999 of the above-identified application. Please amend the application as follows.

**IN THE CLAIMS**

OK to enter 8/9  
C  
J  
50. (amended) A method for forming a photoresist relief image comprising:  
applying a coating layer of a photoresist composition on an integrated circuit substrate or  
a liquid crystal display substrate, the photoresist composition comprising a resin binder, a  
photoactive component and a polymeric dye that contains one or more polycyclic chromophores,  
said dye compound being a polymer wherein the polymer has a weight average molecular weight  
of at least about 5,000; and  
exposing and developing the photoresist composition coating layer to provide a  
photoresist relief image.

Please add the following new claims.

07/22/1999 RWIMBUSH 00000003 041105 08726613

01 FC:102

156.00 CH  
60. A method for forming a photoresist relief image comprising:

applying a coating layer of a photoresist composition on a substrate, the photoresist  
composition comprising a photoactive component and a dye compound that comprises an